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Sheet 1 of 1

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE
(Modified) PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
08425ZP

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10784377

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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(Use several sheets if necessary)APPLICANT
Richard Van Court Carr, et al..

FILING DATE

GROUP

(37 CFR 1.98(b))

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| EXAM- INER DATE | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE IF APPROPRIATE |
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EXAMINER

R. Karp

DATE CONSIDERED

4/15/06

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1449 (05/23/06)

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Complete If Known

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|-------------------------------|---------------------------------------|
| Application Number | 10/784,377 |
| Filing Date | 02/23/2004 |
| First Named Inventor | Richard Van Court Carr, et al. |
| Art Unit | 1752 |
| Examiner Name | |
| Attorney Docket Number | 06425ZP USA |

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| | | Country Code ² Number ³ Kind Code ⁴ <small>(if known)</small> | | | | |
| lu | | WO 00/67072 | 11/08/2000 | Du Pont | | |
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